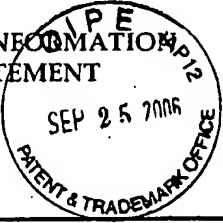


FORM PTO - 1449				ATTORNEY DOCKET NO.: ASC-022CPC1			
SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT				APPLICANTS: Wu <i>et al.</i>			
				SERIAL NO.: 10/603,852			
				FILING DATE: June 25, 2003 GROUP: 2811			
U.S. PATENT DOCUMENTS							
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	A269	2002/0063292	05/30/2002	Armstrong			
	A270	2002/0167048	11/14/2002	Tweet et al.			
	A271	2004/0007715	01/15/2004	Webb et al.			
	A272	2004/007724	01/15/2004	Murthy et al.			
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<i>OK</i>	B55	0 828 296 A	03/11/1998	EP					
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	C167	International Search Report and Written Opinion from the International Examining Authority for related application PCT/US01/19613, dated June 22, 2002							
DWO	C168	Kuboto M., et al. "New SOI CMOS Process with Selective Oxidation, " IEEE IEDM TECH, DIG., pp. 814-816 (1986)							
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